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PATENTS  
MIC-20

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

PATENT APPLICATION

Applicant : Pary Baluswamy et al.  
Application No.:  
Filed : Herewith  
For : PATTERN MASK WITH FEATURES TO  
MINIMIZE THE EFFECT OF ABERRATIONS

New York, New York 10020  
March 1, 2002

Hon. Commissioner for Patents  
Washington, D.C. 20231

INFORMATION DISCLOSURE STATEMENT

Sir:

Pursuant to 37 C.F.R. §§ 1.56 and 1.97, applicants hereby make the following patents and publications of record in the above-identified patent application:

Wald et al. U.S. Patent 5,932,491 (August 3, 1999)  
Pierrat et al. U.S. Patent 6,120,952  
(September 19, 2000)  
Stanton et al. U.S. Patent 6,144,109 (November 7, 2000)  
Stanton U.S. Patent 6,214,497 (April 10, 2001)  
Futrell et al. U.S. Patent 6,238,824 (May 29, 2001)  
Stanton et al. U.S. Patent 6,242,816 (June 5, 2001)  
Futrell et al. U.S. Patent 6,245,468 (June 12, 2001)  
Stanton et al. U.S. Patent 6,258,489 (July 10, 2001)  
Pierrat et al. U.S. Patent 6,284,419 (September 4, 2001)  
Pierrat et al. U.S. Patent 6,319,644 (November 20, 2001)  
Pierrat et al. U.S. Patent Application Publication No. 2001/0002304A1 (May 31, 2001)

Futrell et al. U.S. Patent Application Publication  
No. 2001/0023043A1 (September 20, 2001)  
Pierrat et al. U.S. Patent Application Publication  
No. 2001/0023045A1 (September 20, 2001)  
Baggenstoss U.S. Patent Application Publication  
No. 2001/0033979A1 (October 25, 2001)

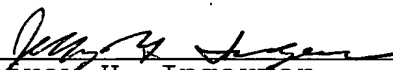
Peterson, J.S., "Analytical Description of Anti-scattering and Scattering Bar Assist Features,"  
Proceedings of SPIE: Optical Microlithography XIII,  
vol. 4000, pp. 77-89 (March 1-3, 2000)

Copies of the aforementioned patents and publications, which are listed on the accompanying Form PTO-1449 (submitted in duplicate), are enclosed herewith.

It is respectfully requested that these patents and publications be (1) fully considered by the Patent and Trademark Office during examination of this application; and (2) printed on any patent which may issue on this application. Applicants request that a copy of Form PTO-1449, as considered and initialled by the Examiner, be returned with the next communication.

An early and favorable action is respectfully requested.

Respectfully submitted,

  
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FORM PTO-1449

U.S. DEPARTMENT OF COMMERCE  
PATENT AND TRADEMARK OFFICEATTY. DOCKET NO.  
MIC-20

APPLN. NO.

INFORMATION DISCLOSURE  
STATEMENT BY APPLICANTAPPLICANT  
Pary Baluswamy et al.FILING DATE  
Herewith

GROUP ART

 jc997 P.S. PTO  
 10/890073  
 03/01/02

## U.S. PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
	5,932,491	8/1999	Wald et al.	438	734	
	6,120,952	9/2000	Pierrat et al.	430	30	
	6,144,109	11/2000	Stanton et al.	257	797	
	6,214,497	4/2001	Stanton	430	5	
	6,238,824	5/2001	Futrell et al.	430	5	
	6,242,816	6/2001	Stanton et al.	257	797	
	6,245,468	7/2001	Futrell et al.	430	5	
	6,258,489	7/2001	Stanton et al.	430	5	
	6,284,419	9/2001	Pierrat et al.	430	30	
	6,319,644	11/2001	Pierrat et al.	430	30	
	2001/0002304A1	5/2001	Pierrat et al.	430	30	
	2001/0023043A1	9/2001	Futrell et al.	430	5	
	2001/0023045A1	9/2001	Pierrat et al.	430	30	
	2001/0033979A1	10/2001	Baggenstoss	430	5	

## FOREIGN PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
						YES	NO

## OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

EXAMINER INITIAL	
	Peterson, J.S., "Analytical Description of Anti-scattering and Scattering Bar Assist Features," Proceedings of SPIE: Optical Microlithography XIII, vol. 4000, pp. 77-89 (March 1-3, 2000)

EXAMINER

DATE CONSIDERED

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not conformance and not considered. Include copy of this form with next communication to applicant.